Special Issue

Microwave Applications in Chemical Engineering

Message from the Guest Editors

This Special Issue on “Microwave Applications in Chemical Engineering” aims at showing the most recent advances in dielectric properties measurement, microwave material interaction, industrial applications of microwave energy, modelling of microwave power applications, microwave plasma applications, microwave chemistry, microwave assisted biomass and waste processing, medical and biological applications of microwave, microwave processing design and optimization, and microwave assisted preparation of new materials.

Guest Editors

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